

Title: METHOD OF MANUFACTURING A SEMICONDUCTOR
DEVICE CAPABLE OF ETCHING A MULTI-LAYER OF ORGANIC
FILMS AT A HIGH SELECTIVITY

Inventor(s): Hiroto OHTAKE, et al.

Filing Date: February 22, 2002

Serial No.: 10/080,848

Docket No.: KRM-00101

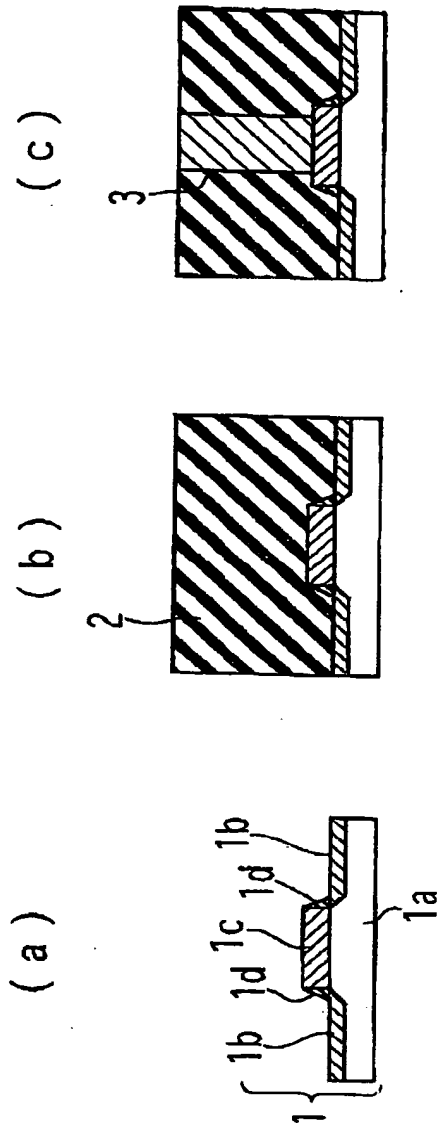


FIG.19
PRIOR ART

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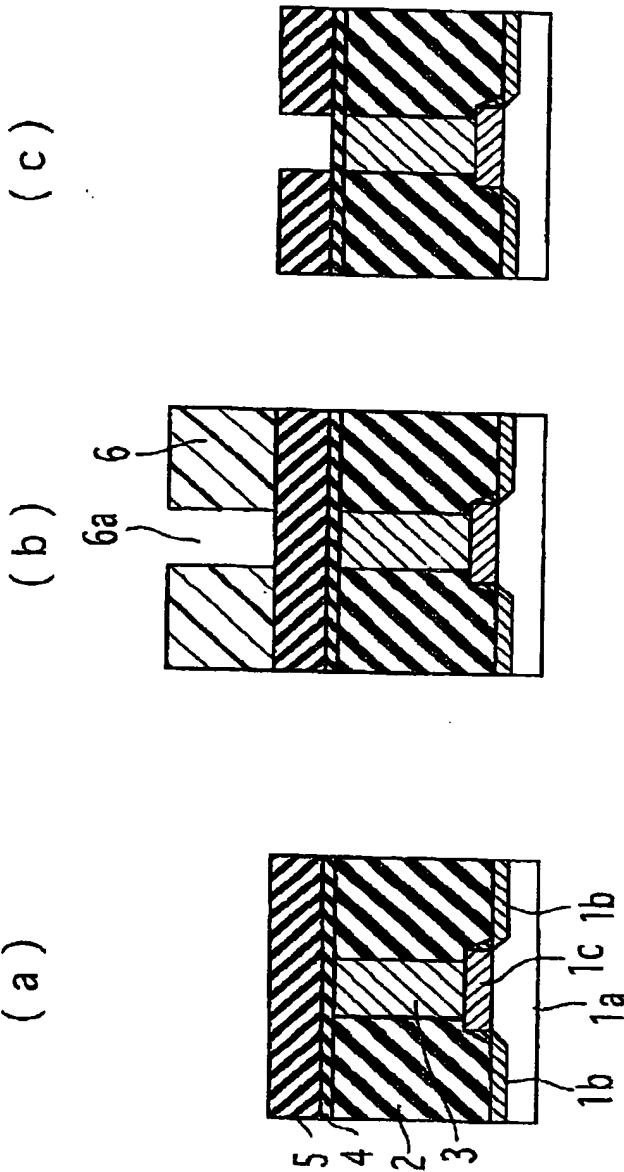


FIG.20
PRIOR ART

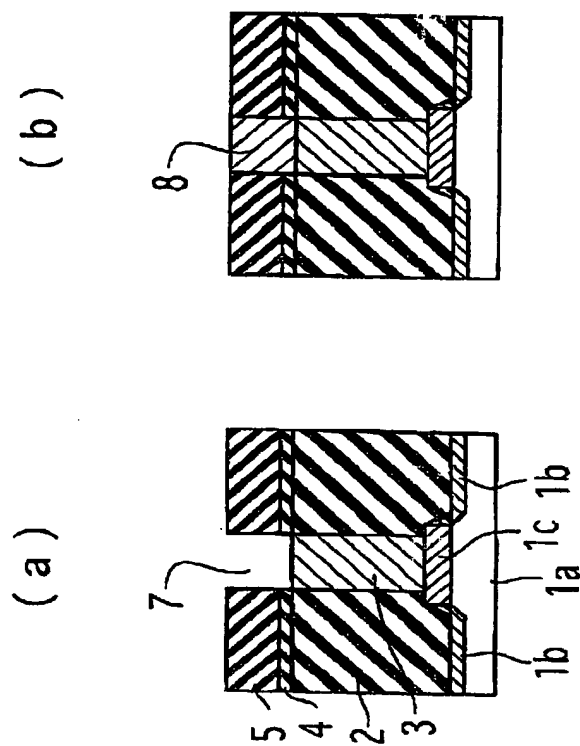
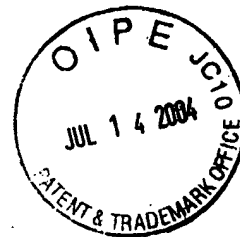


FIG.21
PRIOR ART

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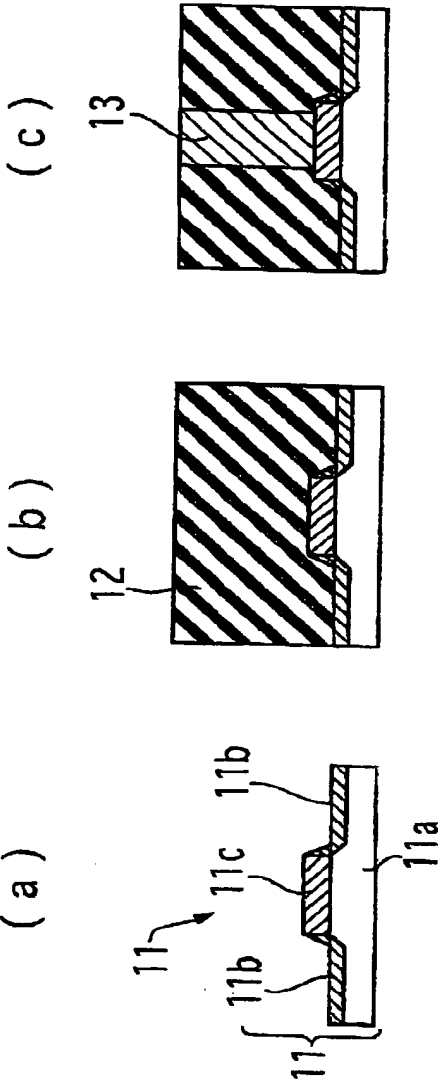


FIG.22
PRIOR ART

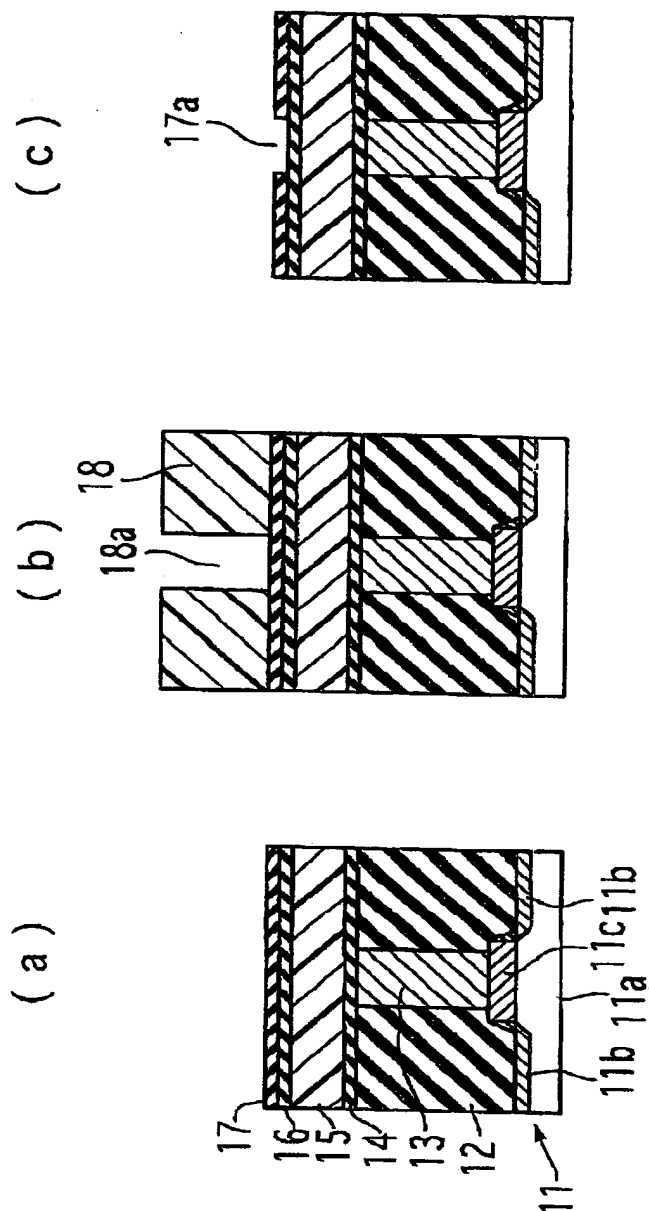


FIG. 23
 PRIOR ART

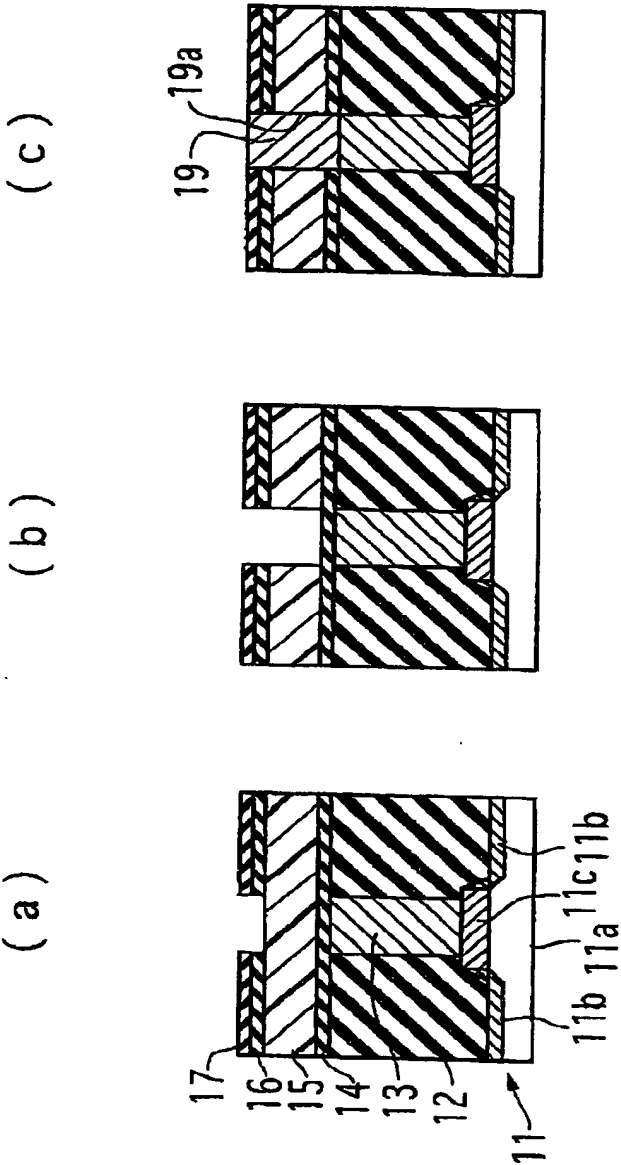


FIG.24
PRIOR ART

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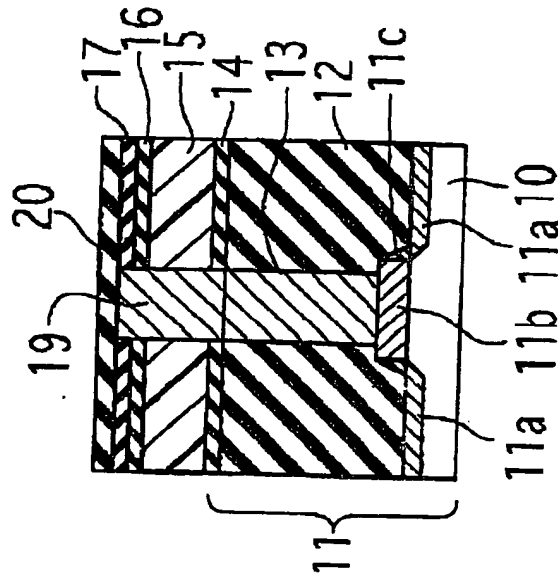


FIG. 25

PRIOR ART